## High-performance monolayer MoS<sub>2</sub> field-effect transistors and photodetectors on SiO<sub>2</sub> gate dielectric passivated with cyclic olefin copolymer

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Trap states of the semiconductor/gate dielectric interface give rise to a pronounced subthreshold behavior in field-effect transistors (FETs) diminishing and masking intrinsic properties of 2D materials. To reduce the well-known detrimental effect of SiO<sub>2</sub> surface traps, this work spin-coated an ultrathin ( $\approx$ 5 nm) cyclic olefin copolymer (COC) layer onto the oxide and this hydrophobic layer acts as a surface passivator. The chemical resistance of COC allows to fabricate monolayer MoS<sub>2</sub> FETs on SiO<sub>2</sub> by standard cleanroom processes. This way, the interface trap density is lowered and stabilized almost fivefold, to around 5 × 10<sup>11</sup> cm<sup>-2</sup> eV<sup>-1</sup>, which enables low-voltage FETs even on 300 nm thick SiO<sub>2</sub>. In addition to this superior electrical performance, the photoresponsivity of the MoS<sub>2</sub> devices on passivated oxide is also enhanced by four orders of magnitude compared to nonpassivated MoS<sub>2</sub> FETs. Under these conditions, negative photoconductivity and a photoresponsivity of 3 × 10<sup>7</sup> A W<sup>-1</sup> is observed which is a new highest value for MoS<sub>2</sub>. These findings indicate that the ultrathin COC passivation of the gate dielectric enables to probe exciting properties of the atomically thin 2D semiconductor, rather than interface trap dominated effects.

## References

[1] S.B. Kalkan, E. Najafidehaghani et al., Adv. Optical Mater. 11 (2023) 2201653.



Figures

